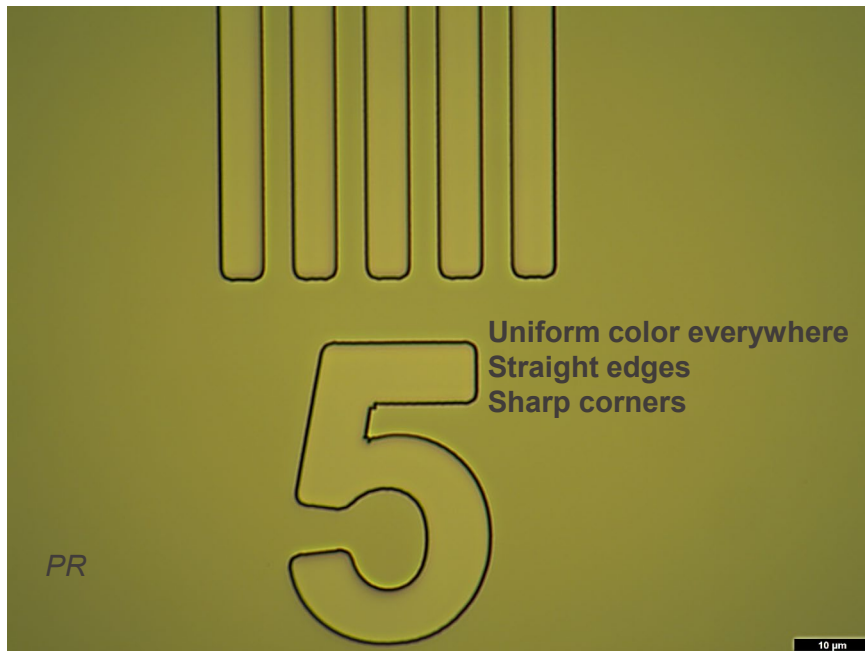


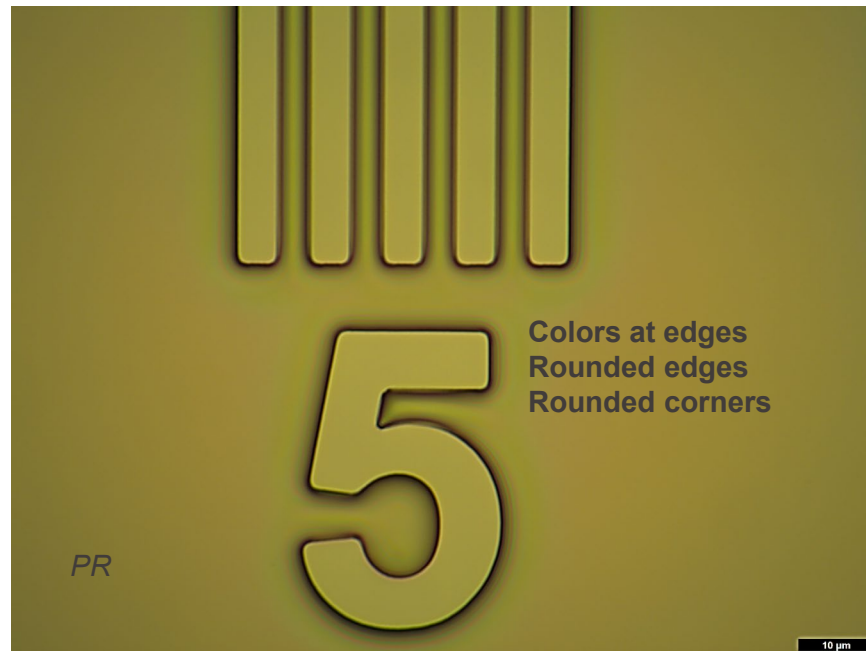
Silicon test wafer
Ti/Pt sputtered (Spider)

Litho AZ10xt 1um (ACS + MA6)

No Reflow



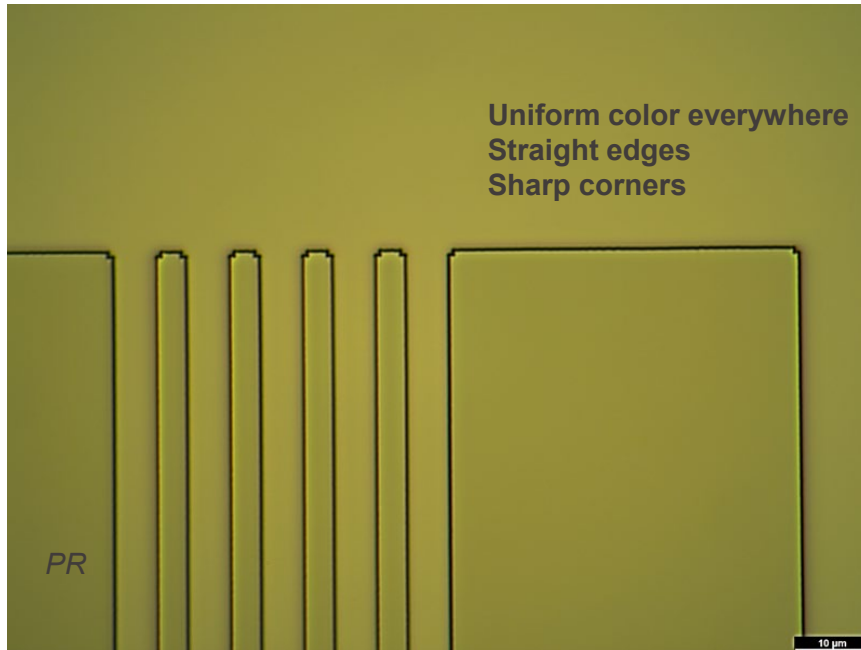
Reflow 2min @125°C



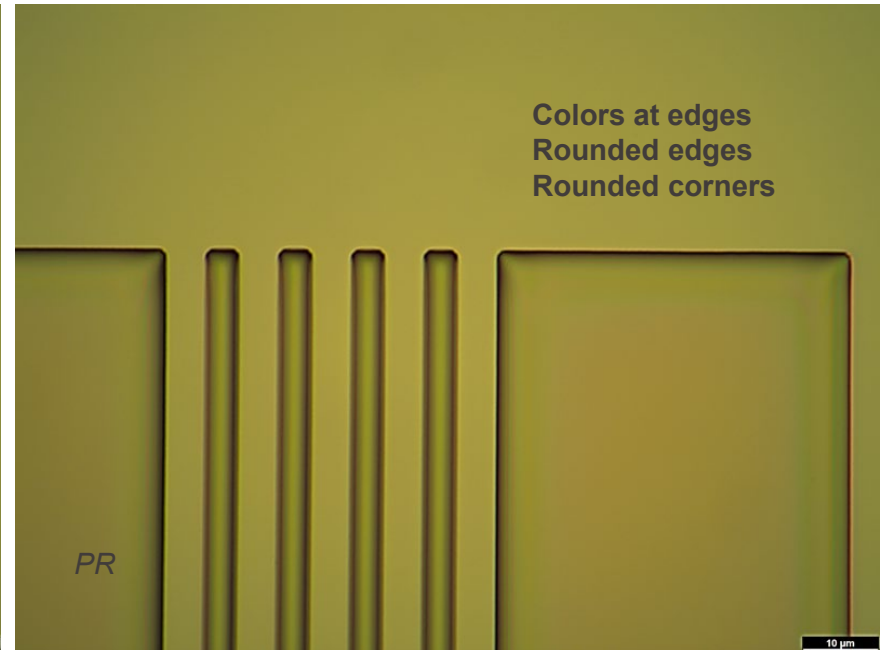
Silicon test wafer
Ti/Pt sputtered (Spider)

Litho AZ10xt 1um (ACS + MA6)

No Reflow



Reflow 2min @125°C



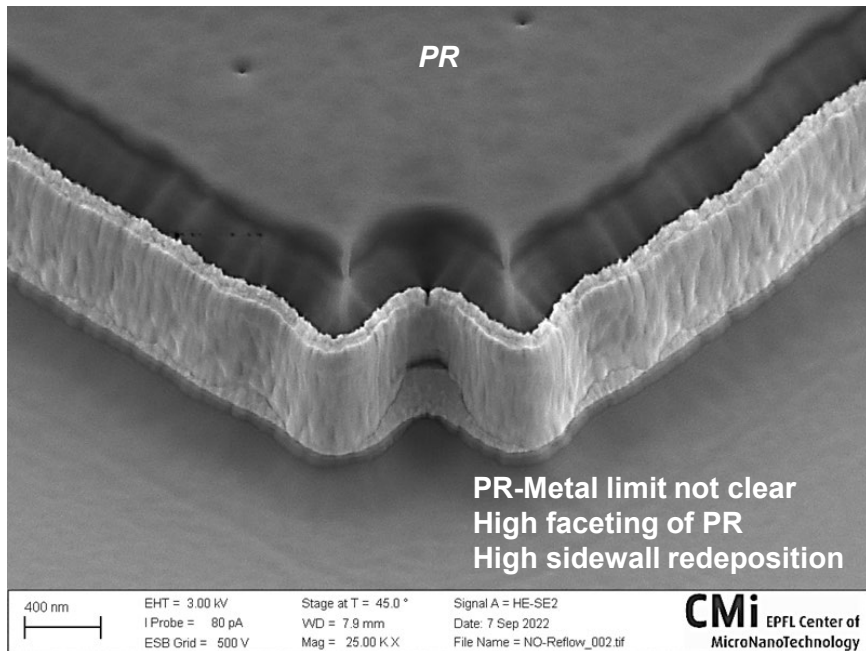
Photoresist reflow for IBE etch process

Ti/Pt sputtered (Spider)

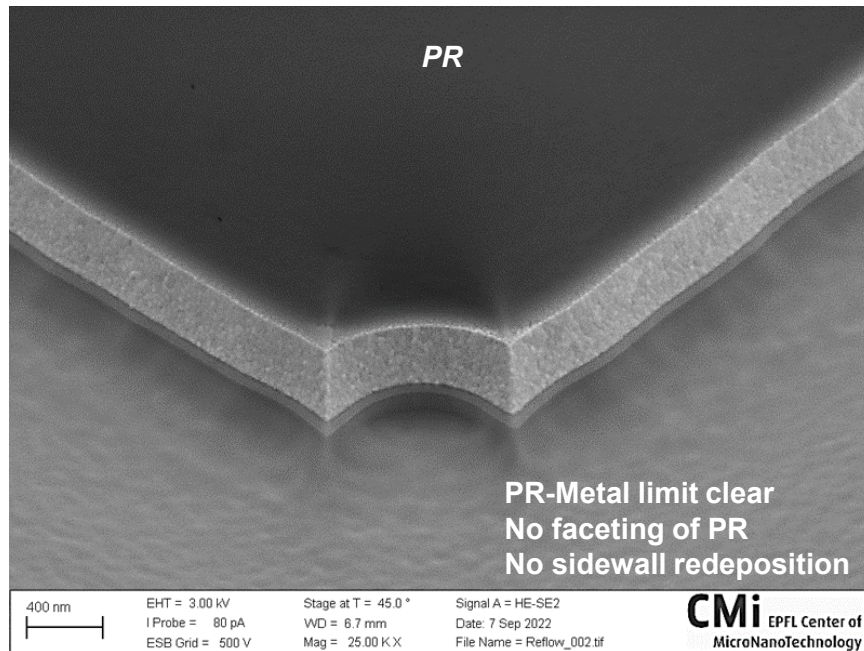
Litho AZ10xt 1um (ACS + MA6)

Medium_IBE, -10deg, 50% over-etch

No Reflow



Reflow 2min @125°C

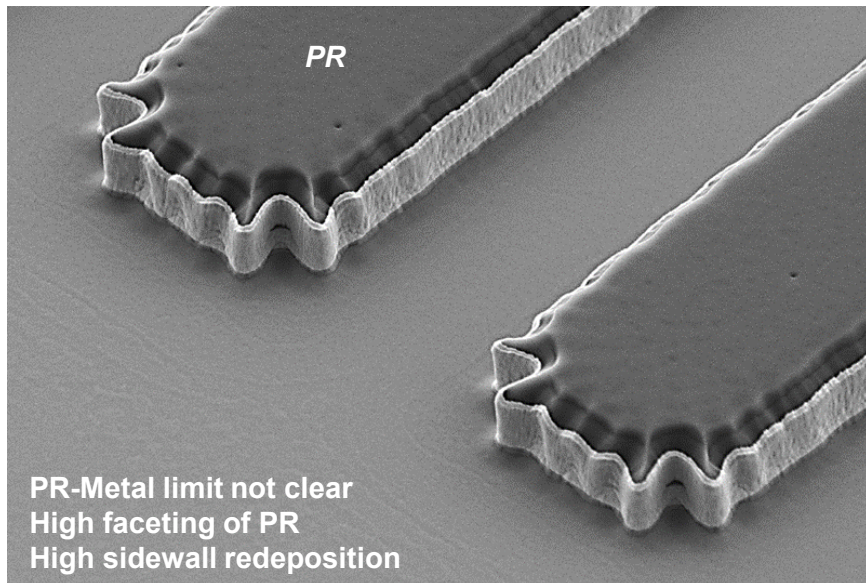


Ti/Pt sputtered (Spider)

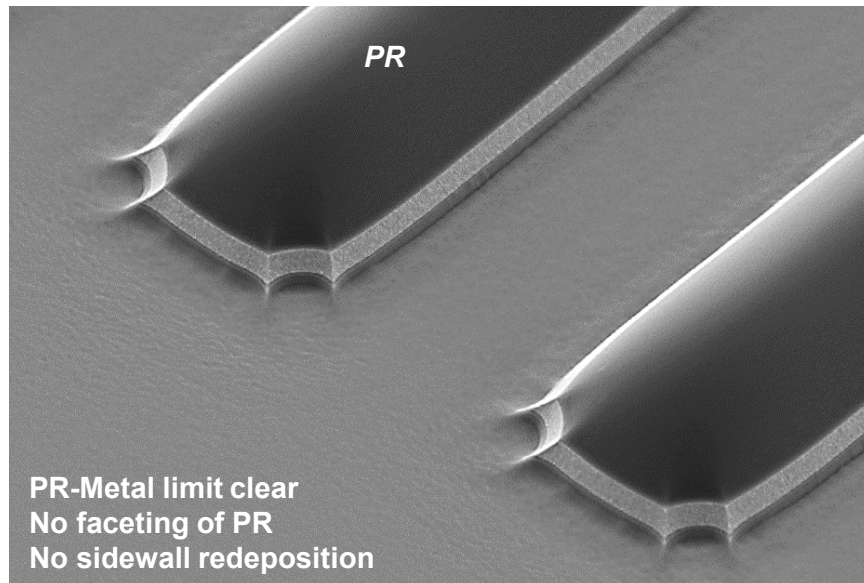
Litho AZ10xt 1um (ACS + MA6)

Medium_IBE, -10deg, 50% over-etch

No Reflow



Reflow 2min @125°C



EHT = 3.00 kV
I Probe = 80 pA
ESB Grid = 500 V

Stage at T = 45.0 °
WD = 7.9 mm
Mag = 10.00 K X

Signal A = HE-SE2
Date: 7 Sep 2022
File Name = NO-Reflow_004.tif



EHT = 3.00 kV
I Probe = 80 pA
ESB Grid = 500 V

Stage at T = 45.0 °
WD = 6.7 mm
Mag = 10.00 K X

Signal A = HE-SE2
Date: 7 Sep 2022
File Name = Reflow_004.tif

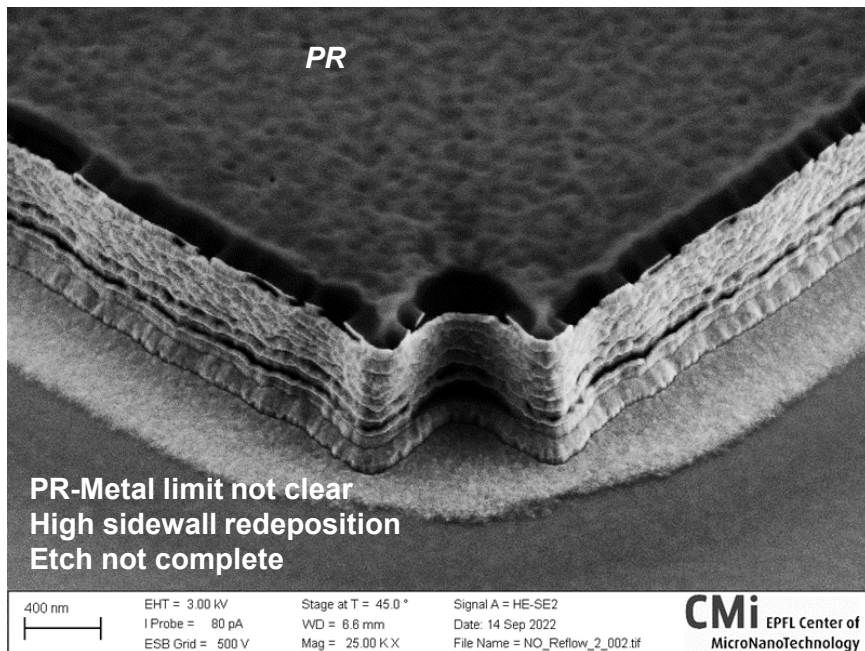
Photoresist reflow for IBE etch process

Ti/Pt sputtered (Spider)

Litho AZ10xt 1um (ACS + MA6)

Medium_IBE, 70% @ -45deg, 30% @ -5deg, 10% over-etch

No Reflow



Reflow 2min @125°C

